

Notice of References Cited

Application/Control No.

09/838,513

Applicant(s)/Patent Under
Reexamination
CHEN ET AL.

Examiner

Julio J. Maldonado

Art Unit

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,937,325	08-1999	Ishida	438/655
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	K	US-			
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FOREIGN PATENT DOCUMENTS

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	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Mouroux, Aliette; The Reactive Formation of TiSi ₂ in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999, pages
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))
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